Thermo. Titr. Application Note No.H-100Title:Determination of total acids in highly acidic
etch solutions

Scope:	Determination	of	the	total	acids	concentration	in
	mixtures of nitr	ic-h	ydrof	luoric	acid int	tended for etch	ing
	silicon substrat	es.					

Principle:Direct thermometric titration of a weighed amount of
nitric-hydrofluoric acid etch solution with standard 2
mol/L sodium hydroxide.

Reagents:	Titrant: Standard 2 mol/L sodium hydroxide solution,
	standardized against potassium hydrogen phthalate.
	Protect titrant in Dosino with a soda-lime guard tube,
	and check the Dosino calibration regularly.

Method:	Basic Experimental Parameters:	Basic Experimental Parameters:				
	Titrant delivery rate (mL/min.)	2.5				
	No. of exothermic endpoints	1				
	Data smoothing factor (DSF)	55				
	Stirring speed (802 stirrer)	6				
	<i>Titration:</i> Weigh accurately ~1g of sed dry titration vessel (e.g., 6.1450. vessel, 10-90mL), and add 30mL with 2 mol/L NaOH to a final end sample analyzed here. Only of observed, probably due to the mini- present.	<i>Titration:</i> Weigh accurately ~1g of solution into a clean dry titration vessel (e.g., 6.1450.210 PFA titration vessel, 10-90mL), and add 30mL D.I. water. Titrate with 2 mol/L NaOH to a final endpoint. Note: in the sample analyzed here. Only one endpoint was observed, probably due to the minute amount of HF present.				

Example:

Etch acid based on undiluted, concentrated 70% HNO₃ Total acids (as % w/w HNO₃) = 69.30±0.04%, n=9





Blank determinations:





Automated Titrotherm system with sample processor